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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
08/994,038	12/18/1997	SHUNPEI YAMAZAKI	07977/208001	6059
26171	7590 09/30/2004	EXAMINER		INER
FISH & RICHARDSON P.C. 1425 K STREET, N.W.		COLEMAN, WILLIAM D		
11TH FLOO	•		ART UNIT	PAPER NUMBER
WASHINGT	ON, DC 20005-3500		2823	

DATE MAILED: 09/30/2004

Please find below and/or attached an Office communication concerning this application or proceeding.

n — —	Application No.	Applicant(s)				
	08/994,038	YAMAZAKI ET AL.				
Office Action Summary	Examiner	Art Unit				
•	W. David Coleman	2823				
The MAILING DATE of this communication a Period for Reply	ppears on the cover sheet with the c	orrespondence address				
A SHORTENED STATUTORY PERIOD FOR REP THE MAILING DATE OF THIS COMMUNICATION - Extensions of time may be available under the provisions of 37 CFR after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a re - If NO period for reply is specified above, the maximum statutory perio - Failure to reply within the set or extended period for reply will, by state Any reply received by the Office later than three months after the mai earned patent term adjustment. See 37 CFR 1.704(b).	1. 1.136(a). In no event, however, may a reply be tined things the statutory minimum of thirty (30) day of will apply and will expire SIX (6) MONTHS from the cause the application to become ABANDONE	nely filed s will be considered timely. the mailing date of this communication. D (35 U.S.C. § 133).				
Status						
1) Responsive to communication(s) filed on 25	September 2004					
	<u> </u>					
· <u>-</u>						
,—	closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.					
Disposition of Claims						
4) ☐ Claim(s) 2,6,11,12,14 and 16-26 is/are pend 4a) Of the above claim(s) is/are withdress 5) ☐ Claim(s) is/are allowed. 6) ☐ Claim(s) 2,6,11,12,14 and 16-26 is/are reject 7) ☐ Claim(s) is/are objected to. 8) ☐ Claim(s) are subject to restriction and	rawn from consideration.					
Application Papers						
9) The specification is objected to by the Exami	ner.					
10)☐ The drawing(s) filed on is/are: a)☐ accepted or b)☐ objected to by the Examiner.						
Applicant may not request that any objection to th	Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).					
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).						
11)☐ The oath or declaration is objected to by the	Examiner. Note the attached Office	Action or form PTO-152.				
Priority under 35 U.S.C. § 119						
 12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a) All b) Some * c) None of: 1. Certified copies of the priority documents have been received. 2. Certified copies of the priority documents have been received in Application No 3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)). * See the attached detailed Office action for a list of the certified copies not received. 						
Attachment(s)						
1) Notice of References Cited (PTO-892)	4) 🔯 Interview Summary					
 Notice of Draftsperson's Patent Drawing Review (PTO-948) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/0 Paper No(s)/Mail Date 	Paper No(s)/Mail D. 5) Notice of Informal F 6) Other:	Patent Application (PTO-152)				

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DETAILED ACTION

Claim Rejections - 35 USC § 103

- 1. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 2. Claims 2, 6, 12, 14, 16, 18, 19,12, 22, 23, 24, 25 and 26 are rejected under 35 U.S.C. 103(a) as being unpatentable over Inoue et al., U.S. Patent 5,873,003 in view of Okada et al., U.S. Patent 5,582,640.
- 3. Pertaining to claim 2, <u>Inoue</u> discloses a semiconductor device substantially as claimed. See **FIGS. 1-50**, where <u>Inoue</u> teaches a semiconductor device comprising:
- a plurality of photodiodes 403 (as seen in FIG. 22) being formed in a matrix on an insulating surface 1609;

a plurality of vertical charge coupled devices on the insulating surface, said vertical charge coupled devices being connected with the plurality of photodiodes; (see FIG. 16);

at least a horizontal charge coupled device on the insulating surface, said horizontal charge coupled device being connected with the vertical charge coupled devices, wherein at least one of the vertical and horizontal charge coupled devices comprises a crystalline semiconductor film having a plurality of crystals extending in a crystal growth direction,

wherein a crystal structure of the crystalline semiconductor film 1753 in the crystal growth direction is continuous so that a charge moving is not restricted by a grain boundary.

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However, <u>Inoue</u> fails to explicitly teach wherein at least one of the vertical and horizontal charge coupled devices that has the crystalline semiconductor film is arranged such that a charge transfer direction of the at least one of the vertical and horizontal charge coupled devices is coincident with the crystal growth direction. <u>Okada</u> teaches that the crystalline semiconductor film is arranged such that a charge transfer direction of the at least one of the vertical and horizontal charge coupled devices is coincident with the crystal growth direction. See FIGS. 1-158(h) where Okada teaches horizontally crystallization, also see FIG. 50(d) where Okada teaches the growth direction of the silicon grain. In view of Okada, it would have been obvious to the crystalline semiconductor film is arranged such that a charge transfer direction of the at least one of the vertical and horizontal charge coupled devices is coincident with the crystal growth direction, because the mobility between the presence and absence of the grain boundary becomes more remarkable (column 62, lines 34-56).

- 4. Pertaining to claim 23, <u>Inoue</u> discloses further an active matrix display device. <u>Okada</u> teaches a semiconductor device to be an active matrix display device. In view of <u>Okada</u>, it would have been obvious to one of ordinary skill in the art to incorporate the active matrix display device of <u>Okada</u> into the <u>Inoue</u> device because a high quality picture is reproduced (column 1, lines 25-27).
- 5. Pertaining to claim 11, <u>Inoue</u> discloses wherein the crystalline semiconductor film 2 is formed over a quartz substrate, and wherein an incident light is made from a side of the quartz substrate (see claim 12 of Inoue).
- 6. Pertaining to claim 12, <u>Inoue</u> discloses wherein the charge transfer direction includes a plurality of directions (polycrystalline film option).

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7. Pertaining to claim 14, <u>Inoue</u> discloses wherein the semiconductor film is a silicon film.

Pertaining to claims 17 and 20, <u>Inoue</u> discloses wherein the crystalline semiconductor film is formed over a quartz substrate.

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8. Pertaining to claims 16 and 19, <u>Inoue</u> discloses a semiconductor device comprising: a crystalline semiconductor film being formed on an insulating surface,

said crystalline semiconductor film having a plurality of crystals extending in a crystal growth direction (polycrystalline) which is parallel to the insulating surface;

an insulating film on the crystalline semiconductor film;

a plurality of electrodes being formed on the insulating film, each of said plurality of electrodes being located within a predetermined distance so that a plurality of MOS capacitors 11 formed between the plurality of electrodes and the crystalline semiconductor film with the insulating film therebetween,

wherein a charge transferred from one of the MOS capacitors to another of the MOS capacitors in a charge transfer direction,

wherein a crystal structure of the crystalline semiconductor film is continuous so that the crystal structure is regarded as single crystal for the charge,

wherein the charge transfer direction is coincident with said crystal growth direction.

- 9. Pertaining to claim 18, <u>Inoue</u> discloses wherein the semiconductor device consist of an image sensor.
- 10. Pertaining to claims 21 and 22, <u>Inoue</u> discloses an image sensor (CCD), which consist of a photodiode.
- 11. Pertaining to claims 25 and 26, <u>Inoue</u> discloses a semiconductor device comprising:

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a photoelectric conversion (silicon interacting with light) formed over an insulating surface:

a charge coupled device electrically connected to the photoelectric conversion device and formed over the insulating surface;

said charge coupled device including:

a crystalline semiconductor film formed on the insulating surface, said crystalline semiconductor film having a plurality of crystals (polycrystalline silicon as taught by Inoue) extending in a crystal growth direction which is parallel to the insulating surface;

an insulating film on the crystalline semiconductor film (MOSFET section);

a plurality of electrodes (having a predetermined distance, which becomes an active matrix display) formed on the insulating film (Inoue teaches forming an array, column 6, lines 8-11) so that a plurality of MOS capacitors are formed between the plurality of electrodes and the crystalline semiconductor film with the insulating film therebetween,

wherein a charge is transferred from one of the MOS capacitors to another of the MOS capacitors in a charge transfer direction,

wherein the charge transfer direction is coincident with the crystal growth direction.

Conclusion

- 12. THIS ACTION IS MADE FINAL. Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).
- 13. A shortened statutory period for reply to this final action is set to expire THREE

 MONTHS from the mailing date of this action. In the event a first reply is filed within TWO

 MONTHS of the mailing date of this final action and the advisory action is not mailed until after

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the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37

CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event,

however, will the statutory period for reply expire later than SIX MONTHS from the mailing

date of this final action.

14. Any inquiry concerning this communication or earlier communications from the

examiner should be directed to W. David Coleman whose telephone number is 703-305-0004.

The examiner can normally be reached on 9:00 AM-5:00 PM. After February 4, 2004, please

call 571-272-1856

15. If attempts to reach the examiner by telephone are unsuccessful, the examiner's

supervisor, Olik Chaudhuri can be reached on 703-306-2794. The fax phone number for the

organization where this application or proceeding is assigned is 703-308-7722.

16. Any inquiry of a general nature or relating to the status of this application or proceeding

should be directed to the receptionist whose telephone number is 703-308-0956.

W. David Coleman Primary Examiner

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